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Form PTO-1449 (MODIFIED)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 032026-0707		SERIAL NO. Unassigned		
<b>INFORMATION DISCLOSURE CITATION</b>  <i>(Use several sheets if necessary)</i>				APPLICANT Ferencz Denes et al.				
				FILING DATE Submitted Herewith		GROUP ART UNIT Unknown		
<b>U.S. PATENT DOCUMENTS</b>								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE	
MDB		4,187,331	Feb. 5, 1980	Hsloh-Lien Ma				
MDB		4,253,888	Mar. 3, 1981	Kikuchi				
MDB		4,264,750	Apr. 28, 1981	Anand et al.				
MDB		4,404,256	Sep. 13, 1983	Anand et al.				
MDB		4,975,144	Dec. 4, 1990	Yamazaki et al.				
MDB		5,190,807	Mar. 12, 1993	Kimock et al.				
MDB		5,445,710	Aug. 29, 1995	Hori et al.				
<b>FOREIGN PATENT DOCUMENTS</b>								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
							YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
MDB		Denes, F. et al., "Influence of RF-Cold Plasma Treatment on the Surface Properties of Paper," <i>J.M.S.-Pure Appl. Chem.</i> , A32(8&9), pp. 1405-1443 (1995); published by Marcel Dekker, Inc.						
MDB		Knight, D. B., "Near-frictionless carbon resists wear and abrasion," <i>Advanced Materials &amp; Processes</i> , p. 14, December 2002; Website: <a href="http://www.anl.gov">www.anl.gov</a> .						
MDB		Cruz-Barba, L. E. et al., "Novel Plasma Approach for the Synthesis of Highly Fluorinated Thin Surface Layers," <i>Langmuir</i> 2002, 18, pp. 9393-9400; published by the American Chemical Society.						
MDB		Bento, Wanderson C.A. et al., "Enhancement in Polymer Hydrophobicity by SF <sub>6</sub> Plasma Treatment," <a href="http://www.sbf1.if.usp.br/eventos/ebfp/6/programa/res0105.pdf">http://www.sbf1.if.usp.br/eventos/ebfp/6/programa/res0105.pdf</a> .						
EXAMINER				DATE CONSIDERED				
				4/6/05				
* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.								

